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(54) SUBSTRATE PROCESSING APPARATUS, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE AND NON-TRANSITORY COMPUTER-READABLE RECORDING MEDIUM

(71) Applicant: **Kokusai Electric Corporation**, Tokyo (JP)

(72) Inventors: **Tetsuaki Inada**, Toyama-shi (JP); **Junya Konishi**, Toyama-shi (JP); **Masaki Murobayashi**, Toyama-shi (JP); **Takeshi Yasui**, Toyama-shi (JP); **Takeo Sato**, Toyama-shi (JP)

(73) Assignee: **Kokusai Electric Corporation**, Tokyo (JP)

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(57) **ABSTRACT**

According to one aspect of the technique of the present disclosure, there is provided a substrate processing apparatus including: a process vessel in which a substrate is processed; an outer vessel configured to cover an outer circumference of the process vessel; a gas flow path provided between the outer vessel and the outer circumference of the process vessel; an exhaust path in communication with the gas flow path; an adjusting valve configured to be capable of adjusting a conductance of the exhaust path; a first exhaust apparatus provided on the exhaust path downstream of the adjusting valve; a pressure sensor configured to measure an inner pressure of the outer vessel; and a controller configured to be capable of adjusting an exhaust volume flow rate of the first exhaust apparatus by controlling the first exhaust apparatus based on a pressure measured by the pressure sensor.